TED STATES PATENT AND TRADEMARK OFFICE

PATENT 5310-03000 Fee Only

Application No.: 09/744.877

Confirmation No.: 8711

Filing Date: January 29, 2001

Halimaoui et al.

Inventors: Title:

PROCESS FOR FORMING AN OXIDE LAYER OF

NON-UNIFORM THICKNESS ON THE SURFACE OF A SILICON

SUBSTRATE

Examiner:

Novacek, Christy L.

Art Unit: 2822 Atty. Dkt. No:

5310-03000

CERTIFICATE OF MAILING UNDER 37 C.F.R. \$1.8 DATE OF DEPOSIT:

## REQUEST FOR CONTINUED EXAMINATION REQUEST TRANSMITTAL

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(under 37 CFR § 1.114)

09/744,877, filed on January 29, 20 OF NON-UNIFORM THICKNESS	nination under 37 C.F.R. § 1.114 of application number 101, entitled PROCESS FOR FORMING AN OXIDE LAYER S ON THE SURFACE OF A SILICON SUBSTRATE.
Inventors(s): Aomar Halimaoui,	André Grouillet
Examiner: Novacek, Christy L.	Group/Art Unit: 2822
Assignee: France Telecom	Recorded at Reel 011545, Frame 0952
Correspondence Address in Prior	Eric B. Meyertons
Application:	Conley, Rose, & Tayon, P.C.
•••	P.O. Box 398

## Application Elements

1.	⊠Fi	ling	Fee
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A Fee Authorization Form authorizing a deposit account debit for the RCE fee (\$770.00) required under 37 C.F.R. § 1.17(e) is enclosed.

2. Information Disclosure Statement (IDS)

 ☐ Copies of IDS Citations

 ☐ Form(s) PTO-1449 (1 page)

3. Amendme							
⊠	Αn	amendm	ent is e	nclosed	١.		

Enter the unentered amendment previously filed on \_\_\_\_ under 37 C.F.R. § 1.116. Please consider the arguments in the response filed on \_\_\_

00000001 501505 89744877 under 37 C.F.R. § 1.116.

91 FC:1891

02 FC:1251 118,88 DA

778.98 DA